

## Magnetoelectric properties of double barrier magnetic tunnel junctions with variable Co-Fe-B middle free layer

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Double barrier magnetic tunnel junction (DBMTJ) is interesting from the physical and the application point of view due to higher  $V_{1/2}$  value (at which the zero bias TMR value is halved) and also suitable for investigating the spin-polarized electron coherent tunneling and oscillatory tunnel magneto-resistance effect.<sup>[1-4]</sup> Moreover, it has potential application for developing spin-transistors.

In this work, double barrier magnetic tunnel junctions with the elliptic size of  $2 \times 4 \pi \mu\text{m}^2$  and stack layer structure of Ru(5)/Cu(10)/Ni<sub>79</sub>Fe<sub>21</sub>(5)/Ir<sub>22</sub>Mn<sub>78</sub>(12)/Co<sub>60</sub>Fe<sub>20</sub>B<sub>20</sub>(4)/Al(1.2)-O/Co<sub>60</sub>Fe<sub>20</sub>B<sub>20</sub>( $d$ )/Al(1.2)-O/Co<sub>60</sub>Fe<sub>20</sub>B<sub>20</sub>(4)/Ir<sub>22</sub>Mn<sub>78</sub>(12)/Ni<sub>79</sub>Fe<sub>21</sub>(5)/Ru(5) (layer thickness unit: nm, and  $d=0.8, 1.0, 1.25, 2.0, 3.0, 4.0, 5.1, 6.2, 7.0, 8.0, 10.0, \text{ and } 12.0$  nm) were micro-fabricated. The magneto-electric properties of these DBMTJs with variable Co-Fe-B middle free layer were investigated.

Our experimental results shown that when the  $d < 1.25$  nm the DBMTJ has small TMR ratio like granular MTJ properties, when the  $1.25 \text{ nm} \leq d \leq 12.0$  nm the DBMTJ has large TMR ratio like normal MTJ properties, and when the  $d = 6.2$  nm the DBMTJ has maximum TMR ratio of 59.4% as shown in Fig.1.

Fig.2 shows the TMR curves and bias dependence of the normalized TMR value measured at room temperature (RT) for a typical DBMTJ with  $d = 4.0$  nm after annealed at 275 °C for an hour. The TMR value of 43% and resistance-area product (RS) of  $3.76 \text{ k}\Omega \cdot \mu\text{m}^2$  were obtained at RT. The  $V_{1/2}$  values are estimated to be over than 1.5 V up to 1.9 V (extrapolated) for positive and negative bias. The  $V_{1/2}$  enhancement is produced by the reduction of the effective bias voltage applied to the individual two barriers. It can be seen that there is a slightly asymmetric bias voltage dependence of the TMR, which is distinctly improved compared with that in the reference [3] ( $V_{1/2}$  of +1.44 and -0.72V for positive and negative bias). The asymmetry is due to the subtle differences in the Co-Fe-B/Al-O interfaces. Such DBMTJs are promising candidates for spin-electronic device applications.

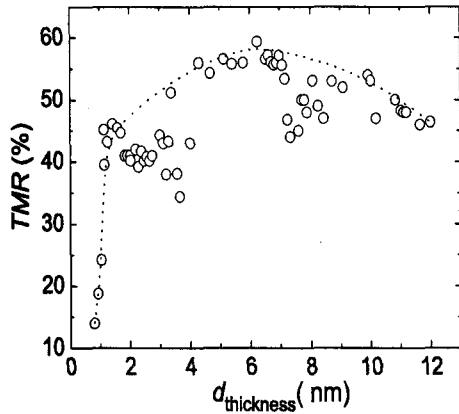


Fig.1 The thickness dependence of  $\text{Co}_{60}\text{Fe}_{20}\text{B}_{20}$  middle free layer versus TMR ratio for the DBMTJs at room temperature.

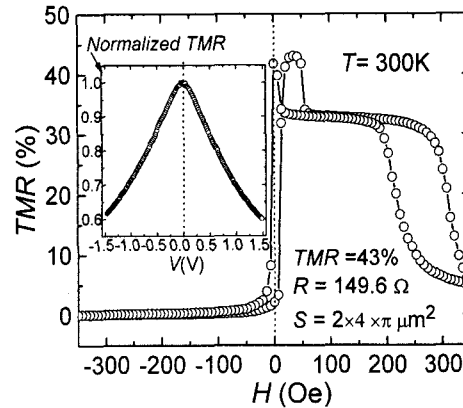


Fig.2 TMR major curves and the bias dependence of normalized TMR (inset) measured at RT for a typical DBMTJ with  $d=4.0$  nm.

### Reference

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